## Nanolevitation Phenomena in Real Plane-Parallel Systems due to the Balance between Casimir and Gravity Forces

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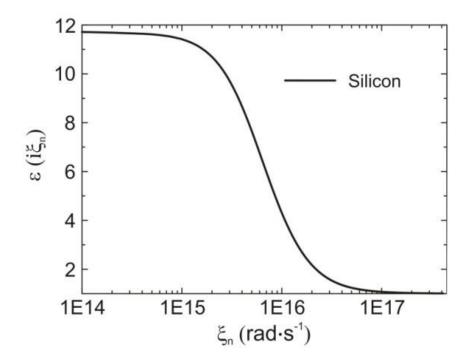


Figure S1: Dielectric permittivity evaluated at Matsubara frequency,  $\varepsilon(i\xi_n)$ , of Si (with a doping level  $1.1 \cdot 10^{15}$  cm<sup>-3</sup> and resistivity 0.077 ( $\Omega$ •cm)<sup>-1</sup>) for an extended frequency range.

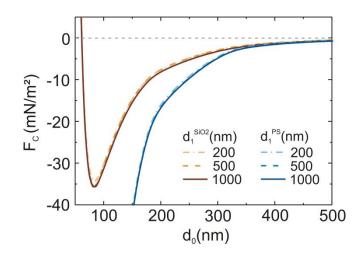


Figure S2: Casimir force (at room temperature) acting on thin films of silica (SiO<sub>2</sub>) and polystyrene (PS) immersed in glycerol over a silicon (Si) substrate, as a function of the separation distance,  $d_0$ . Film thicknesses of  $d_1 = 200,500,1000$  nm are considered.

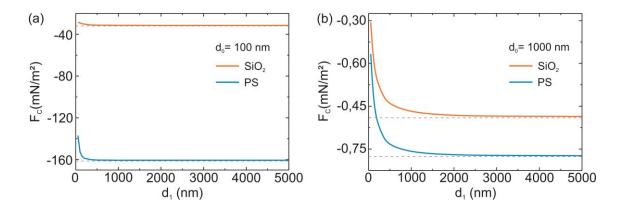


Figure S3: Casimir force as a function of thickness for a single slab of SiO<sub>2</sub> (orange) or PS (blue) inmersed in glycerol over a silicon substrate at (a)  $d_0 = 100$  nm, and (b)  $d_0 = 1000$  nm. The interaction for thick enough slabs tends to the limiting case of two semi-infinite media (displayed with dashed grey lines) as  $d_1$  increases.

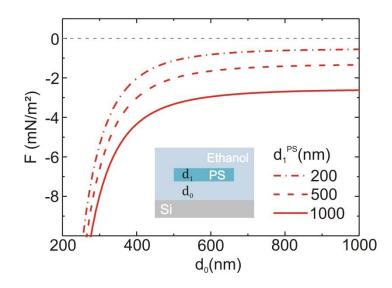


Figure S4: Total force (at room temperature) acting on thin films of PS immersed in ethanol over a Si substrate, as a function of the separation distance,  $d_0$ . Film thicknesses of  $d_1 = 200, 500, 1000$  nm are considered. F( $d_0$ , T) = 0 is marked with light grey lines. In the calculations we consider,  $\rho_{PS} = 1.05$  g/cm<sup>3</sup>,  $\rho_{ethanol} = 0.79$  g/cm<sup>3</sup>, and the permittivity reported in Ref.[1-3], Ref.[4,5] and Ref.[6] for PS, Si, and ethanol, respectively. In all cases, an attractive (negative) force is displayed, and no equilibrium distances are found.

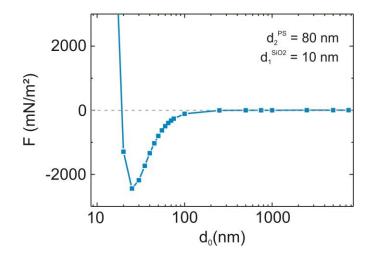


Figure S5: Total force (at room temperature) acting on a bilayer film with a bottom layer made of PS and a thin film of SiO2 on top immersed in glycerol over a silicon substrate. The thickness of the SiO2  $(d_2^{SiO_2})$  is fixed to 10 nm and the thickness of the PS  $(d_1^{PS})$  to 80 nm. The figure shows how the sign of the total force changes with the separation distance  $(d_0)$ . In this system we find two values of  $d_{eq}$ ,  $(d_{eq}^{stable} \sim 20 \text{ nm} \text{ and } d_{eq}^{unstable} \sim 1600 \text{ nm})$  where the lower corresponds to a stable equilibrium position (*F* changes from positive to negative values) and the other one to an unstable equilibrium distance (*F* changes from negative to positive values).

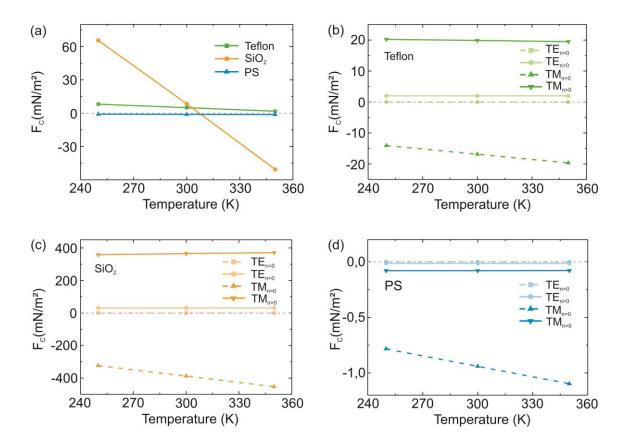


Figure S6: (a) Casimir force as a function of temperature for single layers with thickness fixed to 500 nm immersed in glycerol over a silicon substrate for Teflon, SiO<sub>2</sub> and PS. The gap distance is chosen to be, in each case, that of equilibrium at 300 K in Figure 4 in the main manuscript:  $d_0 = 175$  nm for teflon (green),  $d_0 = 60$  nm for SiO<sub>2</sub> (orange), and  $d_0 = 450$  nm for PS (blue). Casimir force contributions of the *TE* and *TM* polarizations at n = 0 and n > 0 for (b) teflon, (c) SiO<sub>2</sub> and (d) PS.

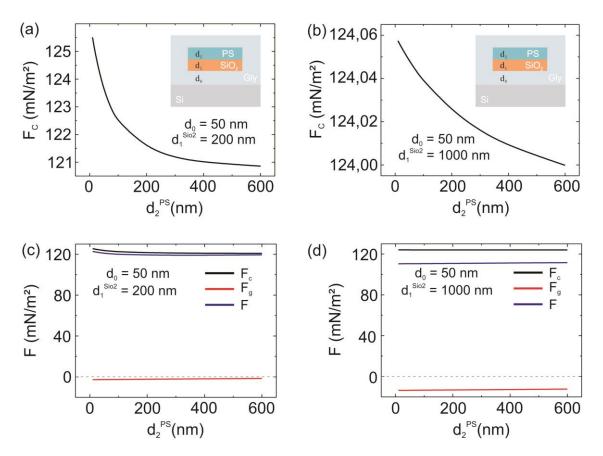


Figure S7: For a bilayer system with a lower SiO<sub>2</sub> layer, and a PS layer on top, immersed in glycerol over a Si substrate a distance  $d_0 = 50$  nm, Casimir force as a function of PS thickness for (a)  $d_1 = 200$  nm and (b)  $d_1 = 1000$  nm. Panels (c) and (d) display the total force, Casimir force and gravity force for the same systems as in panels (a) and (c), respectively.

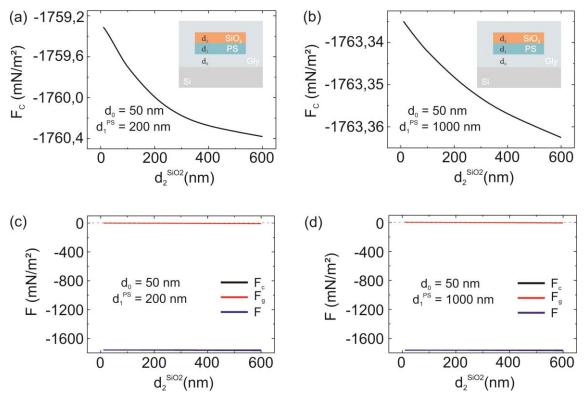


Figure S8: For a bilayer system with a lower PS layer, and a SiO<sub>2</sub> layer on top, immersed in glycerol over a Si substrate a distance  $d_0 = 50$  nm, Casimir force as a function of PS thickness for (a)  $d_1 = 200$  nm and (b)  $d_1 = 1000$  nm. Panels (c) and (d) display the total force, Casimir force and gravity force for the same systems as in panels (a) and (c), respectively.

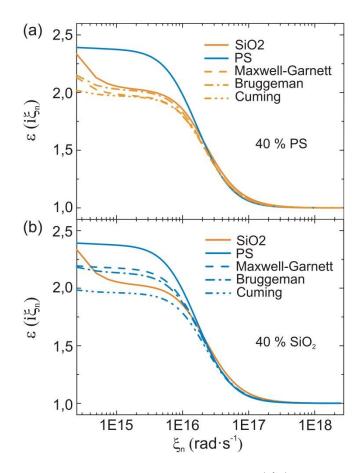


Figure S9: Permittivity evaluated at Matsubara frequencies,  $\varepsilon_{eff}(i\xi_n)$ , according to Maxwell-Garnett, Brugeman, and Cuming models, for f = 0.4 in (a) a SiO<sub>2</sub> matrix with PS inclusions, and (b) the complementary system, i.e., a PS matrix with SiO<sub>2</sub> inclusions. For comparison,  $\varepsilon(i\xi_n)$  of SiO<sub>2</sub> and PS are also displayed.

<sup>&</sup>lt;sup>1</sup> Strom, U.; Hendrickson, J.R.; Wagner, Ri.; Taylor, P.C.; Disorder-induced far infrared absorption in amorphous materials. Solid State Commun. **1974**, 15, 1871-1875.

<sup>&</sup>lt;sup>2</sup> Folks, W. R.; Pandey, S. K.; Pribil, G.; Slafer, D.; Manning, M.; Boreman, G. Reflective infrared

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<sup>&</sup>lt;sup>3</sup> Inagaki; T.: Arakawa, E. T.; Hamm, R. N.; Williams. M. W. Optical properties of polystyrene from the near-infrared to the x-ray region and convergence of optical sum rules. Phys. Rev. B **1977**, 15, 6.

<sup>&</sup>lt;sup>4</sup> Duraffourg, L. Andreucci, P. Casimir force between doped silicon slabs. Phys. Lett. A **2006**, 359, 406–411.

<sup>&</sup>lt;sup>5</sup> Edwards D. F., in: E. D. Palik (Ed.), Handbook of Optical Constant of Solid, vol. 1, second ed., Academic Press, **1985**, p. 547.

<sup>&</sup>lt;sup>6</sup> van Zwol, P. J.; Palasantzas, G. Repulsive Casimir forces between solid materials with high-refractiveindex intervening liquids. Phys. Rev. A **2010**, 81, 062502.